DESCRIPTION

TITLE OF THE INVENTION

Device and Method for Removing Dissolved Oxygen in Alcohol, Alcohol Supply Apparatus and Rinsing Liquid Supply Apparatus

TECHNICAL FIELD

[0001]

The present invention relates to a device and a method for removing dissolved oxygen in alcohol. The present invention also relates to an alcohol supply apparatus and a rinsing liquid supply apparatus that use the device.

BACKGROUND ART

[0002]

When ultrapure water is used in processes for manufacturing semiconductors, the concentration of dissolved oxygen (DO) in the ultrapure water needs to be reduced such that it is, for example, equal to or less than 10ppb, and even such that it is equal to or less than 1ppb, by means of vacuum degasifier or membrane degasifier in order to prevent oxidization of the surface of a substrate.

[0003]

In addition to ultrapure water, many kinds of chemicals are used in semiconductor manufacturing processes. In particular, isopropyl alcohol (IPA) is frequently used as a re-rinsing liquid after rinsing of a substrate and as a drying liquid used in a drying process. At present, the concentration of

DESCRIPTION

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DEVICE AND METHOD FOR ELIMINATING DISSOLVED OXYGEN IN ALCOHOL, ALCOHOL SUPPLY DEVICE, AND CLEANING LIQUID SUPPLY DEVICE

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